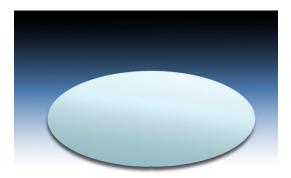
CONTAMINATION

VL ∕ I Standards

Silica Contamination Standards

RAISE YOUR GLASS. The Silica Contamination Standard (SCS) is used to calibrate high-intensity UV tools which size and detect particles on the surface of bare silicon wafers. Use SCS to characterize particles, before particles characterize products.

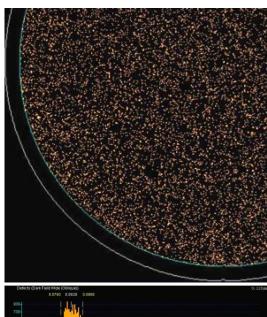
Shown on the left is a Silica Contamination Standard, appearing as a bare wafer to the naked eye. On the right is a particle map and histogram of the same wafer acquired with a Scanning Surface Inspection System.



PRODUCT DESCRIPTION

The Silica Contamination Standard is built by depositing spherical silica spheres which have a very tight monodisperse size distribution. Damage resistant silica spheres are useful for the calibration and monitoring of instruments that measure and count particles with UV and DUV illumination. Available for the first time, silica particles retain their calibration properties from prolonged exposure to UV and DUV light, where other materials may degrade or deform. VLSI Standards supplies Silica Contamination Standards with a variety of sphere sizes in the range of 32 nm up to 1.5 micron.

The calibration certificate includes the approximate number of particles deposited on the wafer. Background contamination is kept at an extremely low level.



PRODUCT SPECIFICATIONS

- SEMI Specification Silicon Wafers
 300 mm and 450 mm diameter silicon wafers
- Silica Spheres
 From 32 nm up to 1.5 micron*
- Traceability
 Silica diameter traceable to SI
- * Sizes in other ranges may be available. Please check with VLSI Standards.

Revision History

Revision	Date	Author	Changes / Comments	
AA	12/9/12	E. Le Roy	Initial Release	

Title: SCS – SPEC SHEET	Doc Number:	Original Release Date: 12/9/12	Page 2 of 2
VLSI Standards Confidential	Revision: AA	Current Release Date: 12/9/12	